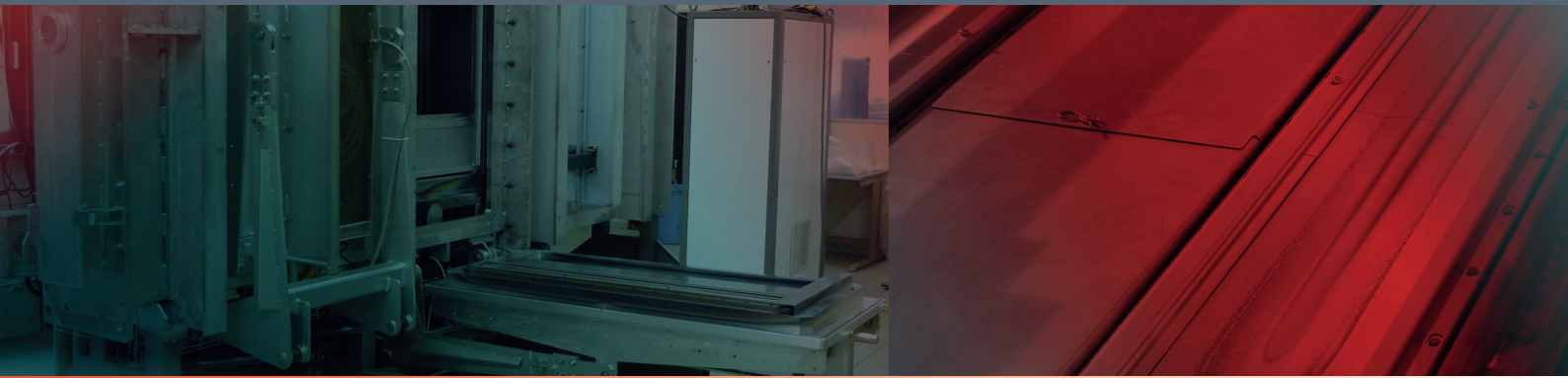


Vacuum ▶ PVD Thin films ▶ Leak testing ▶ Plasma



Vertical large scale PVD sputtering system

LINE1500



Thin films products : uniform deposition on 1 m² substrate

LINE1500 is a thin film deposition system with **vertical substrate handling**. In such a chamber, substrates are handled vertically; their dimensions corresponds to standard PV and flat screens GEN IV. Indeed, this tool owing to its **1.5 m Alliance Concept made magnetron sources**, allows the production of thin **uniform films on a 1 m² surface**.

This system has been designed for double face deposition process also.

Its modular design allows, depending on your process requirements, to combine several deposition modules. The process chamber can also be provided with an external load lock which could be duplicated in output. This industrial equipment has a minimal footprint.



In our workshop, we have at your disposal in our "Lab tool" a LINE 1500 system to demonstrate the feasibility of your thin film coating ideas.

Main features

Ultimate vacuum (turbomolecular configuration) :	5.10 ⁻⁷ mbar ^[1]
Source configuration :	4 x 1500 x 127 mm
Substrate size :	1000 x 1000 mm
Thickness uniformity :	< +/- 5% ^[1]
Surface activation :	<Yes, by glow discharge
Heating :	Yes
Fully automatic system controller :	- Process management - Traceability

^[1] These values have been measured on equipment we have delivered and should be handled as information only. The features of a system depend on its final configuration.

